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Notice of Allowability	Application No.	Applicant(s)	•
	10/748,463	KWON, WON TAIK	
	Examiner	Art Unit	
	Chandra Chaudhari	2891	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED in to or other appropriate communated in the communated in the communated in the communated in the community of the comm	his application. If not include ication will be mailed in due	ed course. THIS
1. This communication is responsive to <u>30 December 2003</u> .			
2. X The allowed claim(s) is/are <u>1-4</u> .			
3.  The drawings filed on 30 December 2003 are accepted by	the Examiner.		
<ul> <li>4.  Acknowledgment is made of a claim for foreign priority u <ul> <li>a)  All b)  Some* c)  None of the:</li> <li>1.  Certified copies of the priority documents hav</li> <li>2.  Certified copies of the priority documents hav</li> <li>3.  Copies of the certified copies of the priority do International Bureau (PCT Rule 17.2(a)).</li> <li>* Certified copies not received:</li> </ul> </li> <li>Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.</li> </ul>	e been received. e been received in Application ocuments have been received i	No n this national stage applica	
5. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which giv	nitted. Note the attached EXAN res reason(s) why the oath or d	MINER'S AMENDMENT or N eclaration is deficient.	OTICE OF
6. CORRECTED DRAWINGS ( as "replacement sheets") mu (a) including changes required by the Notice of Draftsper 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in the second sheet.	son's Patent Drawing Review (  - 's Amendment / Comment or ir  1.84(c)) should be written on the	n the Office action of	back) of
<ol> <li>DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT</li> </ol>	osit of BIOLOGICAL MATER FOR THE DEPOSIT OF BIOL	RIAL must be submitted. N OGICAL MATERIAL.	Note the
Attachment(s)  1. ☑ Notice of References Cited (PTO-892)  2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)  3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date  4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview Sum Paper No./M 08), 7. ☒ Examiner's Ar	rmal Patent Application (PTC nmary (PTO-413), ail Date mendment/Comment tatement of Reasons for Allo	·
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An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Richard Streit on June 20, 2005.

The application has been amended as follows:

In claim 1, line 7, after "cell area", insert --, the peripheral circuit area, and the scribe line--;

line 9, delete "-type";

line 9, delete "both", and insert --the--;

line 10, after "circuit area", insert -- and scribe line--;

line 11, after "CMP", insert --with respect to--;

line 19, delete "the", and insert --a--;

line 19, delete "an", and insert --the--.

In claim 3, line 2, after "for", insert --the--.

In claim 4, line 2, after "for", insert --the--.

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The following is an examiner's statement of reasons for allowance:

The prior art does not disclose to implant impurities into an exposed portion of the silicon substrate, which is not covered with the ion implantation mask, performing a wet dipping for the oxide layer to a resultant structure of the silicon substrate so as to recess the oxide layer filled in the trench of the scribe line, and removing the ion implantation mask as claimed.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Chandra Chaudhari whose telephone number is 571-272-1688. The examiner can normally be reached on Mon - Fri (9:00-5:30).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Bill Baumeister can be reached on 571-272-1722. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Chandra Chaudhari Primary Examiner Art Unit 2891

Chandra Chaudhari June 20, 2005

C Chaudhari